



IN THE UNITED STATES PATENT AND TRADEMARK OFFICE
WASHINGTON, D.C. 20231

Inventor: **Endisch et al.**

Serial No: **09/943,237**

Filed: **August 29, 2001**

For: **Electronic Devices and
Methods of Manufacture**

Examiner: **Maria F. Guerrero**

Art Unit: **2822**

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PRELIMINARY AMENDMENT

The Honorable Commissioner
of Patents and Trademarks
Washington, D.C. 20231

Dear Sir:

This paper responds to the Final Office Action dated October 21, 2002. Please enter the following:

IN THE CLAIMS

Please cancel claims 21-23. The Applicant will pursue these claims in a divisional application.

Please enter the following: (Non-amended claims presented in italics)

12. *A method of forming a shallow trench isolation structure, comprising:*

forming a trench in a substrate having a surface, and depositing a first compound into the trench using spin-on deposition;

partially removing the first compound from the trench such that an upper surface of the compound is below the surface of the substrate; and